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MIO 0060 V3/ 98-0814.03

METHOD OF FABRICATING A SEMICONDUCTOR DEVICE

FIELD OF THE INVENTION

The present invention relates to the field of semiconductors and, more particularly, to an improved dielectric for increasing semiconductor performance.

CROSS-REFERENCES TO RELATED APPLICATIONS

This application is a divisional of U.S. Patent Application
now PAT 6,670,231
Serial No. 10/273,667 filed October 18, 2002 which is a
divisional of U.S. Patent Application Serial No. 09/653,096,
filed August 31, 2000, *now PAT 6,576,964*.

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This application is related to commonly assigned U.S. Patent
now PAT 6,410,968
Application Serial Nos.: 09/653,639, METHOD FOR FORMING A BARRIER
(1)
LAYER TO INCREASE SEMICONDUCTOR DEVICE PERFORMANCE, filed August
NOW PAT 6,521,544
31, 2000, by Powell et al. and 09/653,298, METHOD FOR FORMING A
(1)
DIELECTRIC LAYER AT A LOW TEMPERATURE, filed August 31, 2000, by
Mercaldi et al., the disclosures of which are incorporated herein
by reference.